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Applicant Ryoichi INANAMI et al.							
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U.S. PATENT DOCUMENTS							
Examiner Initial*		Document Number	Date	Name	Class	Sub Class	Filing Date If Appropriate
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Sub Class	Translation Yes or No
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
MCH	Inanami, R. et al., "Throughput Enhancement Strategy of Maskless Electron Beam Direct Writing for Logic Device", IEEE-2000 Technical Digest pp.833-836, December 10-13, 2000.						
MCH	Inanami, R. et al., "Exposure Pattern Data Generation Apparatus Associated with Standard Cell Library and Charged Beam Exposure", U.S. Serial No. 09/817,270, filed March 27, 2001.						
Examiner	Mary E. Hogan			Date Considered 12/15/04			
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